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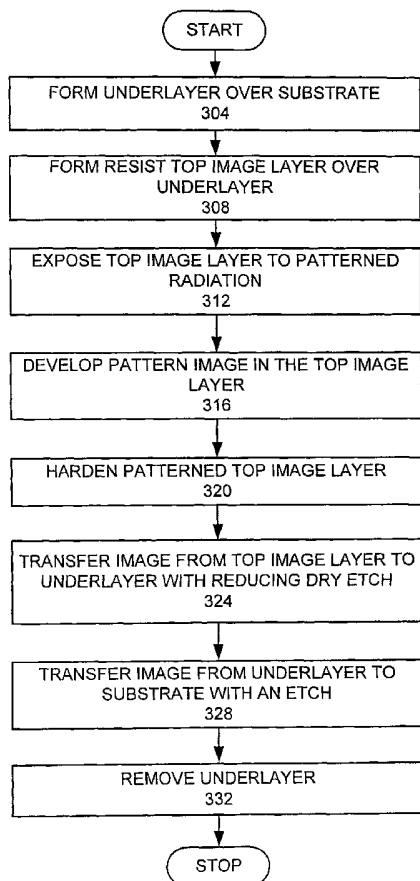
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[Continued on next page]

(54) Title: METHOD PROVIDING AN IMPROVED BI-LAYER PHOTORESIST PATTERN



(57) Abstract: A method for etching a feature in a layer is provided. An underlayer of a polymer material is formed over the layer. A top image layer is formed over the underlayer. The top image layer is exposed to patterned radiation. A pattern is developed in the top image layer. The pattern is transferred from the top image layer to the underlayer with a reducing dry etch. The layer is etched through the underlayer, where the top image layer is completely removed and the underlayer is used as a pattern mask during the etching the layer to transfer the pattern from the underlayer to the layer.

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A. CLASSIFICATION OF SUBJECT MATTER
 IPC 7 G03F7/09 H01L21/768

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)
 EPO-Internal, PAJ, WPI Data, IBM-TDB

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Further documents are listed in the continuation of box C. Patent family members are listed in annex.

° Special categories of cited documents :

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Date of the actual completion of the international search	Date of mailing of the international search report
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Name and mailing address of the ISA European Patent Office, P.B. 5818 Patentlaan 2 NL - 2280 HV Rijswijk Tel. (+31-70) 340-2040, Tx. 31 651 epo nl, Fax: (+31-70) 340-3016	Authorized officer Thiele, N
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